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## books received

The following books have been received by the Editor. Brief and generally uncritical notices are given of works either because of difficulty in finding a suitable reviewer without great delay or in order to inform readers prior to publication of the full review.

### book reviews

Works intended for this column should be sent direct to the Book-Review Editor, whose address appears in this issue. All reviews are also available from **Crystallography Journals Online**, supplemented where possible with direct links to the publisher's information.

### X-ray scattering from semiconductors.

2nd edition. By Paul F. Fewster. World Scientific Publishing, 2003, pp. 316. Price USD 76, GBP 56. ISBN 1 86094 360 8.

This book presents a practical guide to the analysis of materials and includes a thorough description of the underlying theories and instrumental aberrations caused by real experiments. The main emphasis concerns the analysis of thin films and multilayers, primarily semiconductors, although the techniques are very general.

**Epitaxy. Physical principles and technical implementation.** By M. A. Herman, W. Richter and H. Sitter. Pp. xv + 522. Berlin, Heidelberg: Springer-Verlag, 2004. Price hardcover EUR 99.95 net, USD 119.00. ISBN 3 540 67821 2.

In a uniform and comprehensive manner the authors describe all the important aspects of the epitaxial growth processes of solid films on crystalline substrates, e.g. processes in which atoms of the growing film mimic the arrangement of the atoms of the substrate. Emphasis is put on sufficiently fundamental and unequivocal presentation of the subject in the form of an easy-to-read review. A large part of this book focuses on the problems of heteroepitaxy. The most important epitaxial growth techniques which are currently widely used in basic research as well as in manufacturing processes of devices are presented and discussed in detail.

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#### forthcoming meetings

This section carries meetings of interest to crystallographers, including meetings of scientific societies, congresses, summer schools etc. Details of meetings for inclusion, subject to the approval of the Co-editors, should be sent to The Meetings Editor, 5 Abbey Square, Chester CH1 2HU, England.

11–12 October 2004: Santa Barbara, CA, USA. **15th Annual International Light Scattering Colloquium.** For further information contact

Wyatt Technology Corporation, 6300 Hollister

Ave, Santa Barbara, CA 93117-3253, USA (e-mail: info@wyatt.com; WWW: http://www.wyatt.com/events/colloquium/).

# forthcoming meetings and short courses

15–16 October 2004: Madison, WI, USA. 37th SRC Users' Meeting. Current and Future Opportunities in Synchrotron Radiation Research. For further information contact Pamela Layton, Administrative secretary, Synchrotron Radiation Center, 3731 Schneider Drive, Stoughton, WI 53589-3097, USA (email: playton@src.wisc.edu; WWW: http://www.src.wisc.edu/UM2004/default.htm)

18–20 October 2004: Stamford, CT, USA. **Basics of X-Ray Powder Diffraction in Pharmaceuticals.** For further information contact Assa International, 3B East Lake Road Danbury, CT 06811, USA (e-mail: assa.info@assainternational.com; WWW: http://www.assainternational.com/seminars/about.cfm).

18–20 October 2004: Villigen, Switzerland. NOBUGS2004. New Opportunities for Better User Group Software. For further information contact Renate Bercher, Conference Secretary, Paul Scherrer Institut, 5232 Villigen, Switzerland (e-mail: Renate.Bercher@psi.ch; WWW: http://lns00.psi.ch/nobugs2004/).

21–22 October 2004: Stamford, CT, USA. Advanced X-ray Powder Diffraction – Pharmaceutical Application. For further information contact Assa International, 3B East Lake Road Danbury, CT 06811, USA (e-mail: assa.-info@assainternational.com; WWW: http://www.assainternational.com/seminars/about.cfm).

21–23 October 2004: Chicago, IL, USA. FiberNet Fiber Diffraction Workshop. For

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